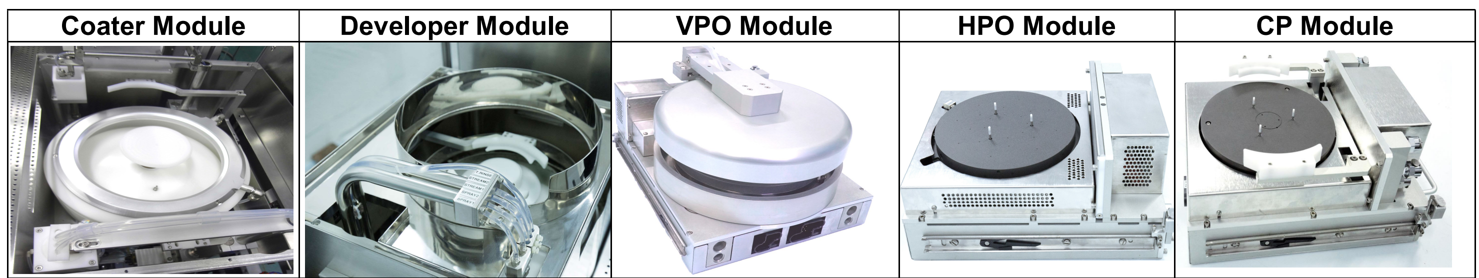
www.picotrack.com

309 Laurelwood Rd #21
Santa Clara, CA 95054
Main: (408)988-7000
Fax: (408)988-7091

PCT-150CRS TRACK SYSTEM

STANDARD PRODUCTION or R&D WITH DUAL TRACKS (1 COATER, 1 DEVLOPER) TOOL SET

Please contact Sales sales@picotrack.com for more information



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<table>
<tr><th>Track System Specification</th><th>Description</th></tr>
<tr><td>System designed</td><td>US Standard System</td></tr>
<tr><td>System Configuration

(*Configuration available upon request)</td><td>
<table>
<tr><td rowspan="4">BLK</td><td>VPO</td><td>HPO</td><td>HPO</td><td>BLK</td><td rowspan="4">BLK</td></tr>
<tr><td>BLK</td><td>BLK</td><td>HPO</td><td>BLK</td></tr>
<tr><td>BLK</td><td>BLK</td><td>CP</td><td>BLK</td></tr>
<tr><td>CP</td><td>CP-CENT</td><td>CP-CENT</td><td>BLK</td></tr>
<tr><td colspan="3">TRACK #1 SHUTTLE ARM</td><td colspan="3">TRACK #2 SHUTTLE ARM</td></tr>
<tr><td rowspan="2">COAT</td><td>SEND</td><td>SEND</td><td>SEND</td><td>SEND</td><td rowspan="2">DEV</td></tr>
<tr><td>REC</td><td>REC</td><td>REC</td><td>REC</td></tr>
</table>
</td></tr>
<tr><td>System dimension</td><td>Length: 93.5” ; Width: 45’’ ; Height: 90’’</td></tr>
<tr><td>Wafer size (workable dual size)</td><td>Up to 6’’ (150mm) or 4’’ & 6’’ auto conversion</td></tr>
<tr><td>Wafer shape</td><td>Round/Square/Rectangular/Triangle/Special</td></tr>
<tr><td>Wafer material</td><td>Silicon/Sapphire/GaAs/ Ceramic…</td></tr>
<tr><td>Wafer sensor</td><td>Optical sensor mapping</td></tr>
<tr><td>System controller</td><td>PC & PLC Controller with Windows OS based</td></tr>
<tr><td>Chemical canister cabinet</td><td>Solvent (EBR, HMDS, Cleaning…), developer liquid</td></tr>
<tr><td>Pumps cabinet</td><td>Photoresist pumps (IDI, Cybor..), dispenser unit, & photoresist bottles</td></tr>
<tr><td>Indexer wafer cassettes capacity</td><td>4 or 8 (available upon request)</td></tr>
<tr><td>Shuttle Robot Arm</td><td>2 Robot Arm and dual end effectors</td></tr>
<tr><td>System Fan Filter Unit (FFU)</td><td>optional</td></tr>
<tr><td>System SECs/GEM</td><td>optional</td></tr>
<tr><td>Coater</td><td>1 module</td></tr>
<tr><td>Catch Cup Set</td><td>Up/down motion</td></tr>
<tr><td>Spindle Unit</td><td>Fixed position</td></tr>
<tr><td>Maximum spin speed</td><td>7000 rpm</td></tr>
<tr><td>Spin motor type</td><td>Servo</td></tr>
<tr><td>Spin speed accuracy</td><td>± 3 rpm</td></tr>
<tr><td>Acceleration range</td><td>0-50000 rpm/sec</td></tr>
<tr><td>Dispense arm accuracy</td><td>± 0.1 mm</td></tr>
<tr><td>Wafer centering</td><td>± 0.1 mm</td></tr>
<tr><td>Dispense arm motion control</td><td>Stepper motor drive and rotation</td></tr>
<tr><td>Dispense arm # 1 & nozzles</td><td>3x or more (3/16’’ or 1/4’’ OD) (Standard)</td></tr>
<tr><td>Dispense arm # 2 & nozzles</td><td>3x or more (3/16’’ or 1/4’’ OD) (Optional)</td></tr>
<tr><td>Dispense method</td><td>Static, and radial</td></tr>
<tr><td>Pre-dispense function</td><td>Yes</td></tr>
<tr><td>Top/Bottom EBR</td><td>Yes</td></tr>
<tr><td>Catch-cup rinse(CCR)</td><td>Optional</td></tr>
<tr><td>Cleaning tip nozzle</td><td>Optional</td></tr>
<tr><td>Humidity & Temperature control</td><td>Optional</td></tr>
<tr><td>Photoresist temperature control</td><td>Optional (≤ 1°C; 10-50°C range)</td></tr>
<tr><td>Coating Type</td><td>Regular, SOG, PG, and Spray (available upon request)</td></tr>
<tr><td>Developer</td><td>1 module</td></tr>
<tr><td>Catch Cup Set</td><td>Up/down motion</td></tr>
<tr><td>Spindle Unit</td><td>Fixed position</td></tr>
<tr><td>Maximum spin speed</td><td>7000 rpm</td></tr>
<tr><td>Spin motor type</td><td>Servo</td></tr>
<tr><td>Spin speed accuracy</td><td>± 3 rpm</td></tr>
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Acceleration range	0-50000 rpm/sec
Spin direction	Clockwise (+) & counter clockwise (-)
Dispense arm motion control	Stepper motor drive and rotation
Dispense arm accuracy	± 0.1 mm
Wafer centering tolerance	± 0.1 mm
Dispense arm # 1 nozzles	1 Spray+ 1 Stream or 2 spray+ 2 stream (Standard)
Dispense arm # 2 nozzles	1 Spray+ 1 Stream or 2 spray+ 2 stream (Optional)
Negative developer nozzles	Cone or fan spray with N2 air assist (Upon request)
Developer dispense type	Stream, Puddle, Fan spray, Cone spray….
Dispense method	Static, radial and sweep
DI water top and back side rinse	Yes
N2 Air Ring back side	Yes
N2 Blow-off top nozzle	Optional
Developer liquid Temp. controller	Optional (≤ 1°C; 10-50°C range)
Vapor Prime Ovent (VPO)	**1 module (Stack up)**
VPO block type	Aluminum anodized with vacuum slots
VPO Temperature controller	Watlow P.I.D with over heating protection
Temperature thermal probe	RTD or TC
Temperature range	Up to 200°C, Δt: 50°C ≤ 200s
Temperature uniformity	± 1°C (25-15°0C), ± 2°C (151-200°C)
HMDS prime method	Fume shower nozzles on top by pressurized N2 with bubbler
Wafer contact angle	≥ 65° on prime silicon wafer
Contact angle uniformmity	≤ 1.5° on prime base silicon wafer
Wafer Carrier	3 pins controlled by stepper motor
Bake method	Contact, vacuum & purge bake
Hot Plate Oven (HPO)	**3 modules (Stack up)**
HPO block type	Aluminum anodized with vacuum slots or standoff proximity
HPO Temperature controller	Watlow P.I.D with over heating protection
Temperature thermal probe	RTD or TC
Temperature range	25-250°C, Δt: 50°C ≤ 200s (>250°C option)
Temperature uniformity	± 1°C (25-150°C), ± 2°C (151-250°C)
Wafer Carrier	3 pins controlled by stepper motor
Bake method	Contact/ Proximity bake/ or fixed proximity
Chill Plate & Centering (CP-CENT)	**4 or 8 modules (Stack up)**
Chill Plate block type	Aluminum anodized with vacuum slots
Chill Plate Temperature control	House cooling water with flowmeter (18°C to 30°C)
Chill method	Contact
Cooling Water Temperature controller	Optional
Wafer carrier	3 pins controlled by stepper motor and cylinder
Wafer Centering	Integrated